

## PATENT ABSTRACTS OF JAPAN

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## (54) MULTI SLIT PROJECTOR

## (57)Abstract:

**PURPOSE:** To provide a slit light line having a uniform light intensity by changing the transmittance of each segment in a shutter array in conformation to the light intensity of each slit light in the slit light line.

**CONSTITUTION:** The light of a light emitting source 1 is diffracted through diffraction gratings 13, 14 after being shaped by a collimator lens 12 to form a two-dimensional spot image 18 in X, Y directions. The light spot groups are continued to each other in one direction to form a slit light line 19 consisting of a plurality of slit lights parallel to Y-direction. The light line 19 is selectively shielded by a liquid crystal shutter 21, whereby a coded slit light output 20 having an optional arrangement is provided. The shutter 21 has transmittances different every slit, and the transmittance of the slit shutter 21 corresponding to each slit light forming the optical line 19 is changed every slit. Even when the light intensity of each slit light is varied, thus, the light intensity of each slit light of the output 20 can be uniformed after being transmitted through the shutter 21.



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